		·			11675.76.1.1		09/0	527,381			
•	INFO	RMATION DISCLOSURE (Use several sheets if necessar		`	Applicant(s) Sandhu, et al.	. ,					
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*EXAMINER INITIAL	REF	DOCUMENT NUMBER	U.S. PATI		NAME	CLASS	SUBCLASS	FILING DATE  IF APPROPRIATE			
TY	A	5,445,996	8/95	Kodera	et al.	438	633				
TY	В	5,486,493	1/96	Jeng		438	623				
<i>ty</i>	С	5,399,235	3/95	Mutsae	rs et al.	438	633				
74	B	5,420,075	5/95	Homma	et al.	438	624	624			
74	E	5,599,740	2/97	Jang et al.		438	626				
<u> 74</u>	F	5,677,239	10/97	Isobe		438	633	633			
74	G	5,795,829	8/98	Shen		438	694				
14	Н	5,708,303	1/98	Jeng		257	758	758			
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FOREIGN PATENT DOCUMENTS											
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)											
M.K. Jain et al., "Advanced Metalization and Interconnect Systems for ULSI Applications: Homogenous and Multilayer Low-K Interlevel Dielectric Architectures for Capacitance Reduction," Conference at University of California, Berkeley, California, October 1996.								layer eley,			
74	Tetsuya Homma, "Fluorinated SiO2 Films for Interlayer Dielectrics in Quarter-Micron ULSI Multilevel Interconnections," Mat. Res. Soc. Symp. Proc., Vol. 381, pp. 239-248, 1995.										
EXAMINER GUACH  DATE CONSIDERED  0 // /0/											
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.											

Docket Number (Optional)

Application Number

## INFORMATION DISCLOSURE CITATION (Use several sheets if necessary) \*EXAMINER INITIAL OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) J. Wary et al., "Vacuum-Deposited Parylene AF-4: A Thermally Stable, Low Dielectric Constant Polymer For Interlayer Dielectric Use," DUMIC Conference, pp. 207-213, February, 1996.

-14	3	J. Wary et al., "Vacuum-Deposited Parylene AF-4: A Thermally Stable, Low Dielectric Constant Polymer For Interlayer Dielectric Use," DUMIC Conference, pp. 207-213, February, 1996.
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